

<b>Search Notes</b> 	<b>Application/Control No.</b>  10/650,601	<b>Applicant(s)/Patent under Reexamination</b>  LIN, SHI-CHI
<b>Examiner</b>  José R. Diaz	<b>Art Unit</b>  2815	

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner
438	409	2/6/2006	JRD
438/429, 431,433,447,450		2/6/2006	JRD